CLAIMS

1. A Ni-based sputtering target material, comprising an alloy having the composition of $(Ni_X\text{-}Fe_Y\text{-}Co_Z)_{100\text{-}W}\text{-}M_W$, wherein:

the M elements are M1 elements;

the M1 elements are one or more elements selected from W, Mo, Ta, Cr, V, and Nb;

the total content W of the M1 elements is 2 to 20 at.%;

the contents of Ni, Fe, and Co are, in at.%,

$20 \leq X \leq 98$,

$2 \leq Y \leq 50$, and

$0 \leq Z \leq 60$, respectively;

the total content of Fe and Co is 1.5 at.% or more; and

the alloy comprises a microstructure that contains a Ni-M phase as a matrix phase, wherein an Fe phase and/or a Co phase are dispersed in the matrix phase, and wherein the microstructure contains an fcc or bcc phase of Fe.

2. A Ni-based sputtering target material, comprising the alloy according to claim 1, wherein:

the alloy comprises, as M elements, M2 elements, wherein the M2 elements are substituted for a part of the M1 elements;

the M2 elements are one or more elements selected from Al, Ga, In, Si, Ge, Sn, Zr, Ti, Hf, B, Cu, P, C, and Ru; and

the total content of the M2 elements is more than 0 to 10 at.%.

3. The Ni-based sputtering target material according to claim 1 or 2, wherein the alloy comprises an fcc or hcp phase of Co.

4. The Ni-based sputtering target material according to any one of claims 1 to 3, wherein the Ni-based sputtering target material has a pass-through-flux of 10% or more.